

Title (en)

Process for obtaining negative images from positive photoresists.

Title (de)

Verfahren zur Herstellung negativer Bilder aus einem positiv arbeitenden Photoresist.

Title (fr)

Procédé pour obtenir des images négatives à partir d'une photoréserve positive.

Publication

EP 0212482 A2 19870304 (DE)

Application

EP 86110953 A 19860808

Priority

US 76470085 A 19850812

Abstract (en)

1. Process for producing negative images from a positive photoresist, by means of the following process steps : A) The preparation of a photosensitive mixture comprising a) about 1 to 25 per cent by weight, based on the solid components of the mixture, of a photosensitive compound of the general formula (I) see diagramm : EP0212482,P12,F1 in which R1 denotes 2-diazo-1,2-benzoquinone-4-sulphonyl, 2-diazo-1,2-naphthoquinone-4-sulphonyl or 2-diazo-1,2-anthraquinone-4-sulphonyl, R2 , R3 and R4 are identical or different and denote hydrogen, R5 , -OR6 or -CO-R7 , R5 and R7 denote alkyl, aryl or aralkyl, and R6 denotes hydrogen, alkyl, aryl, aralkyl or R1 , b) about 75 to 99 per cent by weight, based on the solid components of the mixture, of a novolak or a polyvinylphenol, preferably poly-p-vinylphenol resin, c) about 0.5 to about 20 per cent by weight, based on the solid components of the mixture, of a crosslinking agent which is capable of crosslinking the resin as in b) in the presence of acid produced from the photodecomposition products, and d) a sufficient amount of solvent to dissolve the above compounds, B) the coating of a coating base with the photosensitive mixture as in A), C) the pre-drying of the solution at temperatures in the range 20 to 100 degrees C until the solvent has essentially evaporated, D) image exposure of the photosensitive coating with actinic irradiation, E) the conditioning of the exposed coating at temperatures in the range from at least 95 degrees C to about 160 degrees C over the course of 10 seconds and more, during which time the crosslinking takes place, F) the removal of the non-exposed areas of the coating using an alkaline developer.

Abstract (de)

Die vorliegende Erfindung betrifft ein Verfahren zur Herstellung negativer Bilder aus einem positiv arbeitenden Photoresist. Man stellt ein lichtempfindliches Gemisch, bestehend im wesentlichen aus einem wasserunlöslichen, in alkalischen Lösungsmitteln löslichen Harz, 1,2-Chinon-(2)-diazid-4-sulfonsäureester und einen in Gegenwart von Säure wirkenden Vernetzer in einem Lösungsmittel, her. Nach Aufbringen der Lösung auf einen Schichtträger und Verdunsten des Lösungsmittels wird bildmäßig belichtet, die lichtempfindliche Schicht getempert und die unbelichteten Bereiche durch Entwickeln entfernt.

IPC 1-7

G03F 7/08; **G03F 7/26**

IPC 8 full level

G03C 1/485 (2006.01); **G03F 7/004** (2006.01); **G03F 7/022** (2006.01); **G03F 7/039** (2006.01); **G03F 7/26** (2006.01); **G03F 7/38** (2006.01); **H01L 21/027** (2006.01)

CPC (source: EP KR)

G03C 1/485 (2013.01 - KR); **G03F 7/0226** (2013.01 - EP); **G03F 7/38** (2013.01 - EP)

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Designated contracting state (EPC)

AT DE FR GB NL

DOCDB simple family (publication)

EP 0212482 A2 19870304; **EP 0212482 A3 19871209**; **EP 0212482 B1 19890419**; AT E42419 T1 19890515; CA 1282627 C 19910409; DE 3662952 D1 19890524; HK 71490 A 19900921; JP H0772797 B2 19950802; JP S6238448 A 19870219; KR 870002479 A 19870331; KR 950000236 B1 19950112

DOCDB simple family (application)

EP 86110953 A 19860808; AT 86110953 T 19860808; CA 515742 A 19860812; DE 3662952 T 19860808; HK 71490 A 19900913; JP 18795286 A 19860812; KR 860006618 A 19860812